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(54) PRODUCTION OF NOVOLAK RESIN FOR PHOTORESIST

(57)Abstract:

PROBLEM TO BE SOLVED: To provide a method for producing a novolak resin for a positive-type photoresist, capable of sufficiently controlling its dissolving speed in alkali, and consequently forming such an extremely fine pattern that the line width is 0.30 μ m.

SOLUTION: This method for producing a novolak resin for a photoresist comprises reacting a phenol with an aldehyde using an aromatic hydrocarbon or an aliphatic hydrocarbon as a solvent at a temperature of 150° C in a pressure vessel, then subjecting the reaction product to crosslinking reaction using a crosslinking agent, such as the aldehyde or a dimethiol compound derived from the phenol.

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